

Supplementary Information

Thin-Film Engineering of Mechanical Fragmentation Properties of Atomic-Layer-Deposited Metal Oxides

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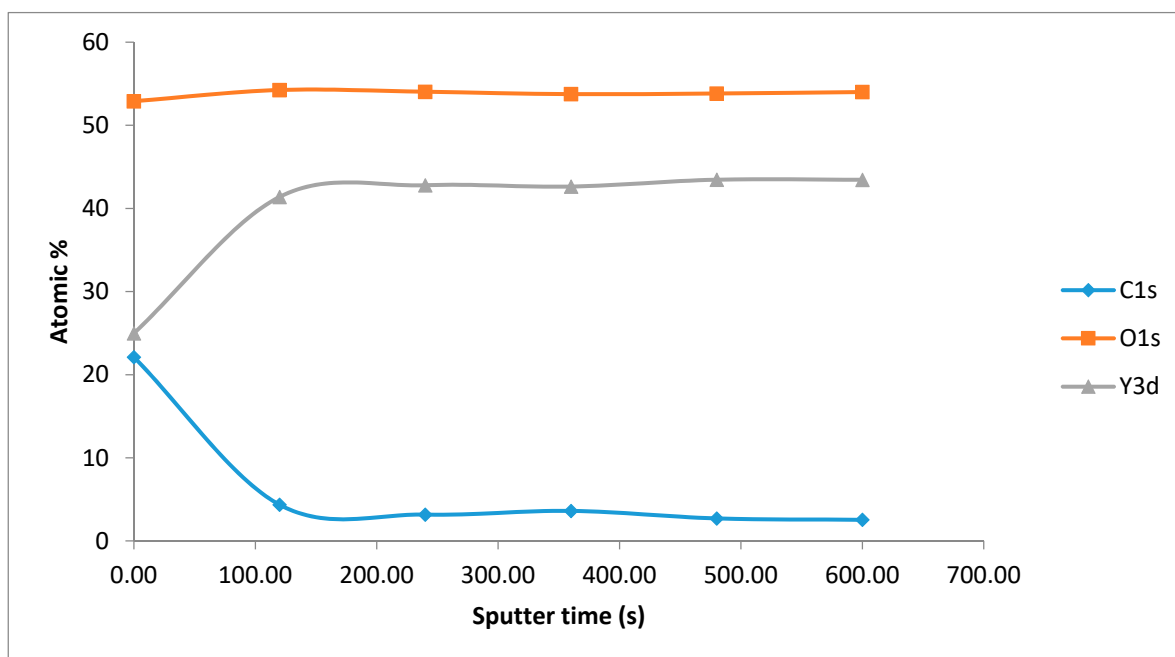


Figure S1. XPS depth profile of Y₂O₃ sample.

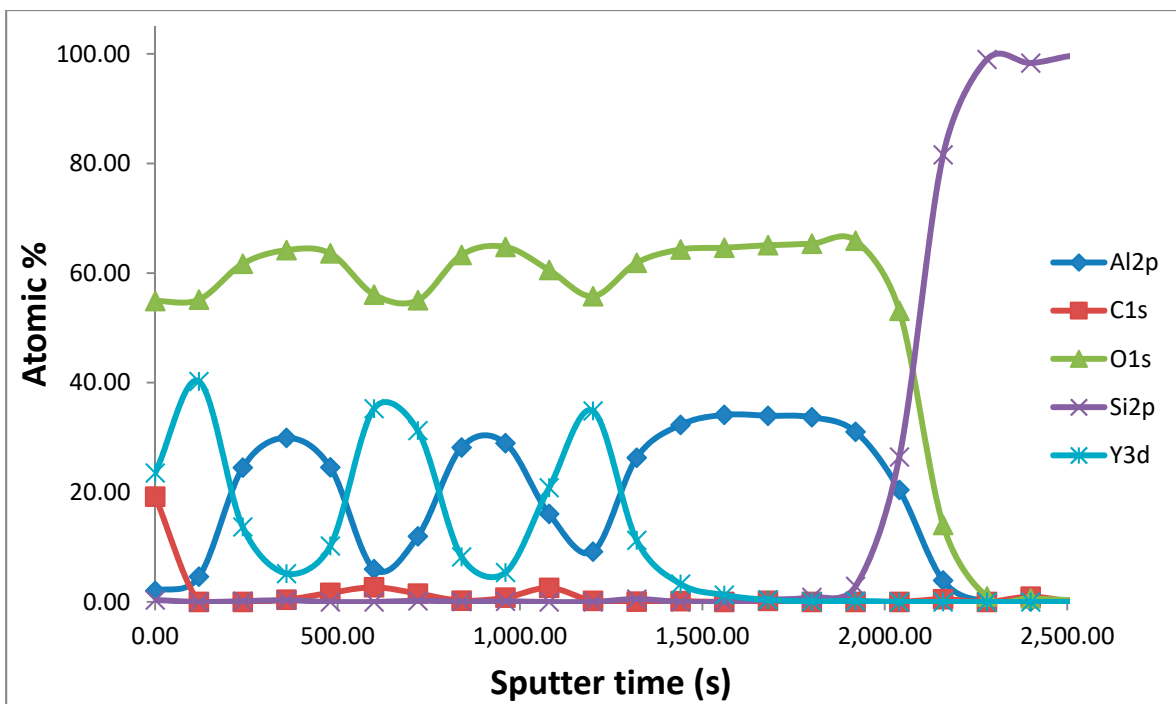


Figure S2. XPS depth profile of 3 × NL (Y₂O₃-Al₂O₃) on Al₂O₃ sample.